AMENDMENTS TO THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 1, line 11, with the following.

-- An exposure apparatus, which transfer the pattern of a master such as a reticle onto a substrate such as a wafer or glass plate, coated with a photosensitive agent, is used to manufacture a device such as a semiconductor device or liquid crystal display device by photolithography. --

Please substitute the paragraph beginning at page 9, line 4, with the following.

-- The photoelectric sensor may be, e.g., a photodiode. In addition to this, any sensor can be employed as ~~far~~ long as it converts light into electrical signals. The memory can employ any arrangement (e.g., a RAM, a ROM, a hard disk, or a logic circuit) as ~~far~~ long as it stores information so as to allow provision of the information. The calculator and/or compensator can employ any arrangement for performing calculation, such as a CPU, which operates in accordance with software, a logic circuit, which has an arithmetic function defined using hardware, or the like. Each of the calculator and compensator may be comprised of a single processor. The light source may be, e.g., an excimer laser. In addition to this, any apparatus or arrangement can be employed as ~~far~~ long as it generates light for exposure. --

Please substitute the paragraph beginning at page 14, line 16, with the following.

-- The second method changes the oscillation frequency of the excimer laser within an arbitrary frequency range below the maximum oscillation frequency. As shown in Fig. 4C, if the

oscillation frequency decreases, the light quantity per unit time decreases. This can obtain the same effect as that obtained when the oscillation duty is low. In the example shown in Fig. 4C, the oscillation frequency is one-quarter that of the example shown in Fig. 4A, and the light quantity per unit time decreases by a factor of ~~4~~ four. Hence, the duty can be expressed as 25[%]. --

Please substitute the paragraph beginning at page 16, line 6, with the following.

-- After a further ~~lapse~~ elapse of time, a change in sensitivity caused by a change in temperature saturates, and the output variation amount saturates. This is because the amount of heat generated on the light-receiving surface of the photoelectric sensor 13 (or 15) by the energy of irradiation light becomes equal to the amount of heat released to its surroundings, and the temperature stabilizes. The output variation amount saturates in a shorter time and becomes larger with increasing energy of light per unit time. --

Please substitute the paragraph beginning at page 17, line 15, with the following.

-- In illuminance uniformity measurement, the illuminance uniformity sensor 13 can be stepped in a slit direction by a regular distance, and the light quality P can be measured after each stepping. When the light quantity P is measured at each step, the illuminance uniformity sensor 13 is irradiated with pulse light having a predetermined number of pulses (e.g., several ~~ten~~ tens of pulses to several ~~hundred~~ hundreds of pulses) while scanning in a scanning direction. The average value of values detected by the illuminance uniformity sensor 13 can be set as the light quantity of each step. --

Please substitute the paragraph beginning at page 17, line 27, and ending on page 18, line 8, with the following.

-- More specifically, the illuminance conformity sensor 13 is irradiated with pulse light as shown in Fig. 7. A region B in Fig. 7 represents a period during which the illuminance uniformity sensor 13 is moved to the next step position. A region A represents a period during which the light quantity of each step is measured. In illuminance uniformity measurement, e.g., pulse light of several ~~ten~~ tens of pulses to several ~~hundred~~ hundres of pulses can be emitted in the region A. --

Please substitute the paragraph beginning at page 19, line 2, with the following.

-- First, in step 1, the characteristic specified by a function $q_{(P)}$ as shown in Fig. 6 is stored in advance in a memory (e.g., a memory 21 in the control system 16) arranged inside or outside the exposure apparatus shown in Fig. 1. The function $q_{(p)}$ will be assumed to be stored in the memory 21 hereinafter. The function $q_{(P)}$ is determined on the basis of actual measurement, e.g., before or after incorporating the photoelectric sensor 13 (or 15). --